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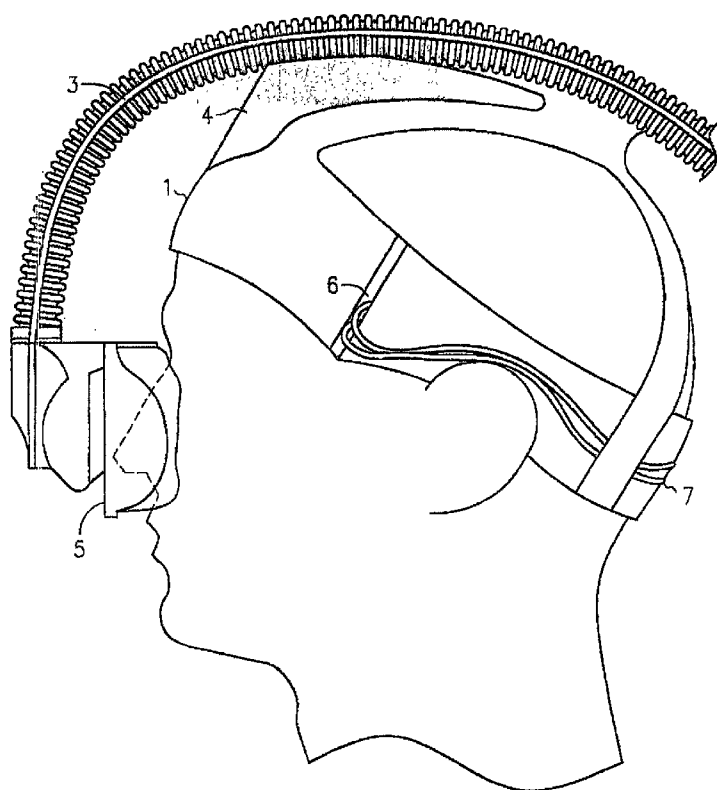
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(54) Title: FACE MASK SUPPORT



(57) **Abstract:** A face mask support for continuous positive airway pressure comprises a hemispheric cap with biasing means support at the medial line of the head. The circumferential edge of the cap extends from the high forehead to below the inion protrusion at the nape of the neck. A biasing means which is preferably of length of spring steel is formed so as to extend from the biasing means support to form a loop around a face mask. The hemispheric cap is formed of an elastic material or is provided with adjustability and the biasing means may be adjusted to accommodate facial configurations and to vary the pressure with which the face mask is apposed to the face. In an alternative embodiment, the support is open and is comprised of a circumferential band extending from the high forehead to below the inion protrusion at the nape of the neck and a medial band extending along the medial line of the head and connecting to the circumferential band at the high forehead and below the inion protrusion. The medial band may be bifurcated at the inion area and each arm of the medial band is connected to the circumferential band near the medial line of the head.